



Ballistic and scattering limited mobility in GaN Single quantum well and Al_{0.25}Ga_{0.75}N/GaN superlattice MOSFET: A Comparative Study.

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Abstract:

In this paper, the authors have calculated the two dimensional mobility in GaN single quantum well and ballistic mobility of Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET as a function of gate length. In the case of two dimensional mobility in GaN single quantum well the different lattice scattering mechanisms, namely ionised impurity scattering and acoustic phonon scattering are taken into account. A comparative study of two dimensional mobility of GaN single quantum well and ballistic mobility Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET has been made.

I. INTRODUCTION:

GaN is a wide bandgap semiconductor and has a large breakdown field, so it is extensively used in high power and high frequency devices[1]. In order to understand the transport characteristics of these materials it is necessary to know the low field two-dimensional mobility of these materials. Terahertz (THz) plasmonic devices such as AlGaN/GaN heterostructures are getting close to being commercialized. In this light, the authors have calculated the two-dimensional mobilities of GaN incorporating acoustic phonon and ionized impurity scatterings. The ballistic Mobility of AlGaN/GaN heterostructure as a function of gate length is also calculated. A comparative study of the mobilities has also been made and the ballistic mobility is higher than the scattering limited mobility. The results agree with the references [2,3].

II. ANALYTICAL MODEL:

In the case of calculation of GaN, the band gaps of AlGaN and GaN are taken as 4.2eV and 3.44 eV respectively [4]. We have assumed the bandgap discontinuity in the well and barrier semiconductors to be distributed to about 60% on the conduction

band and 40% on the valence band. The conduction band offset for the Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET is much higher than the Fermi energy E_f , so the GaN square well can be assumed to be infinite[5].

We consider a rectangular Cartesian coordinate system with z-axis perpendicular to the interfacial planes so that the 2D transport occurs parallel to the xy plane. The electric field ϵ is assumed to be along x-axis and the non-quantizing magnetic field B along z-axis. The carrier distribution function can be written as:

$$f(k) = f_0(E) - \left(\frac{e\hbar}{m^*} \epsilon \right) \frac{\partial f_0}{\partial E} [k_x \xi_x(E) - \omega_B k_y \xi_y(E)]$$

where k is the 2D wave vector of holes with energy E, $f_0(E)$ is the equilibrium Fermi-Dirac function, e is the carrier charge, \hbar is Planck's constant divided by 2π , m^* is the electron effective mass, k_x and k_y are the x- and y-components of k, ω_B is the cyclotron resonance frequency, and ξ_x and ξ_y are the perturbation functions.

The perturbation functions obtained from the Boltzmann transport equation are:

$$\xi_x(E) = \frac{\tau(E)}{1 + \omega_B^2 \tau^2(E)}$$

$$\xi_y(E) = \frac{\tau^2(E)}{1 + \omega_B^2 \tau^2(E)}$$

here, $\tau(E)$ is the combined relaxation time for all the scatterings.

$$\tau^{-1}(E) = \tau_{ac}^{-1}(E) + \tau_{li}^{-1}(E) + \tau_p^{-1}(E)$$

where $\tau_{ac}(E)$ [6] is the relaxation time for acoustic phonon scattering and $\tau_{li}(E)$ [7] is the relaxation time for ionised impurity scattering and $\tau_p(E)$ [8] is the relaxation time for piezoelectric scattering. The Mobility is given by the equation:

$$\mu = \frac{e\tau(E)}{m^*}$$

In the case of calculation of Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET ballistic mobility [9],[10] (i.e. the electron mobility limited by the device contacts given (for the degenerate 2DEG) by :

$$\mu_{bal} = \frac{2 qL}{\pi m_n v_F}$$

Here q is the electronic charge, L is the gate length, m_n is the electron effective mass, v_F is the Fermi velocity, and n_s is the electron sheet density.

III . RESULTS ANALYSIS:

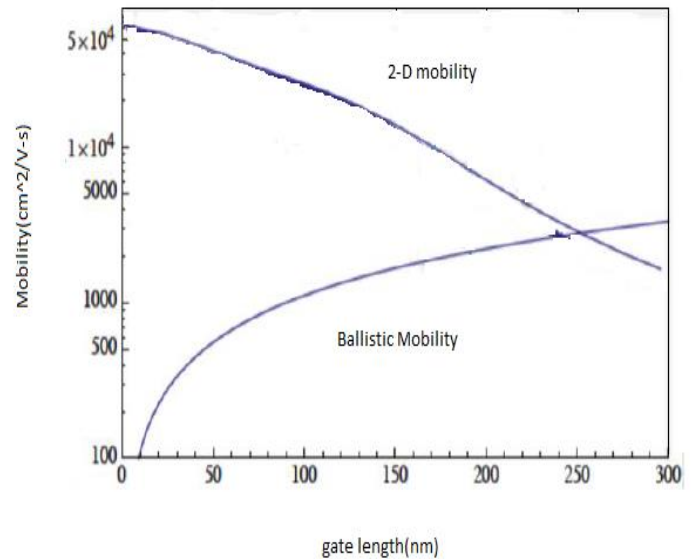


Fig 1: Two dimensional mobility in GaAs and Ballistic Mobility of Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET as a function of gate length.

Figure 1 shows the calculated two dimensional mobility in GaN and Ballistic Mobility of Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET as a function of gate length.[11]

Conclusion:

In the present paper, the authors have made a comparative study of the two dimensional mobility in single GaN quantum well with the Al_{0.25}GaN_{0.75}/GaN Superlattice MOSFET. The results show that the ballistic mobility is quite higher than the scattering limited mobility for 270 nm. So high mobility transistors and the devices can be made with the ballistic channels.

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